AMENDMENTS TO THE CLAIMS

Claims 1-2 (Cancel)

Claim 3 (Currently Amended) A method of dressing a polishing cloth by bringing a dresser in contact with the polishing cloth, comprising:

measuring the height of a surface of the polishing cloth at radial positions of the polishing cloth in a radial direction thereof; and

increasing a rotational speed of the dresser if the surface of the polishing cloth is higher at ~~the~~ an inner circumferential region of the polishing cloth than at an ~~the~~ outer circumferential region of the polishing cloth.

Claim 4 (Currently Amended) A method of dressing a polishing cloth by bringing a dresser in contact with the polishing cloth, comprising:

measuring the height of a surface of the polishing cloth at radial positions of the polishing cloth in a radial direction thereof; and

lowering a rotational speed of the dresser if the surface of the polishing cloth is higher at an ~~the~~ outer circumferential region of the polishing cloth than at an ~~the~~ inner circumferential region of the polishing cloth.

Claim 5 (Currently Amended) A method of dressing a polishing cloth by bringing a dresser in contact with the polishing cloth mounted on a turntable, comprising:

measuring the height of a surface of the polishing cloth at radial positions of the polishing cloth in a radial direction thereof; and

increasing a ratio of a rotational speed of the turntable to a rotational speed of the dresser if the surface of the polishing cloth is higher at an ~~the~~ inner circumferential region of the polishing cloth than at an ~~the~~ outer circumferential region of the polishing cloth.

Claim 6 (Currently Amended) A method of dressing a polishing cloth by bringing a dresser in contact with the polishing cloth mounted on a turntable, comprising:

measuring the height of a surface of the polishing cloth at radial positions of the polishing cloth in a radial direction thereof; and

lowering a ratio of a rotational speed of the turntable to a rotational speed of the dresser if the surface of the polishing cloth is higher at an ~~the~~ outer circumferential region of the polishing cloth than at an ~~the~~ inner circumferential region of the polishing cloth.